

35. (Amended) [An apparatus as claimed in] The apparatus of claim 33 [wherein the liquid reservoir] further [comprises and] comprising an ozone dispersion apparatus [disposed in the liquid chamber for dissolving ozone received at the inlet in liquid contained within the chamber] in the reservoir, and connected to the ozone generator.

36. (Amended) [An apparatus as claimed in] The apparatus of claim 24 [and] further comprising a chamber enclosing [for housing] the workpiece [as it is sprayed with treatment liquid that proceeds from the one or more] and nozzles.

39. (Amended) An apparatus for [providing a mixture of ozone and a liquid comprising water for treatment of] treating the surface of a workpiece, the apparatus comprising:

a liquid reservoir [having a chamber holding the liquid comprising water];  
a pump having an [input] inlet and an outlet, with the inlet connected to receive [the] liquid comprising water] from the [chamber of the] reservoir[, the pump further having an output for supplying pressurized liquid comprising water therefrom];  
[one or more] nozzles disposed to spray [fluid therefrom] liquid onto [the surface of] the workpiece;

a fluid path extending between the [output] outlet of the pump and the [one or more] nozzles[, the fluid path carrying the pressurized liquid comprising water that is provided at the output of the pump; and]

*A2*  
*Sub*  
*B2*

an ozone generator for generating a supply of ozone [at an output thereof]; and

one or more supplying lines extending from the ozone generator to the fluid path for injecting ozone into the fluid path.

45. (Amended) [An apparatus as claimed in] The apparatus of claim 39 [wherein the reservoir further comprises] further comprising an ozone dispersion apparatus [disposed in the chamber for dissolving ozone received at the inlet in the liquid comprising water contained within the chamber] in the reservoir connected to the ozone generator, for dissolving ozone into liquid in the reservoir.

46. (Amended) [An apparatus as claimed in] The apparatus of claim 39 [and] further comprising a chamber enclosing [for housing] the workpiece [as it is sprayed with the liquid comprising water that proceeds from the one or more] and the nozzles.

Please add new claims 79-86 as follows:

79. A system for processing an article, comprising:

a processing liquid reservoir for holding a processing liquid;

a flow path connecting the processing liquid reservoir to a treatment chamber;

a rotor assembly rotatably mounted in the treatment chamber; and

an ozone source connected to deliver ozone into processing liquid flowing from the processing liquid reservoir to the treatment chamber.

80. The system of claim 79 further comprising a dispersion unit in the reservoir and connected to the ozone source.

81. The system of claim 79 further comprising a plurality of spray nozzles in the treatment chamber, with the flow path connected to the spray nozzles.

82. The system of claim 79 further comprising a pump in the flow path, for pumping the processing liquid from the reservoir to the treatment chamber.

83. The system of claim 79 further comprising a mixer in the flow path for mixing the processing liquid and the ozone.

84. A system for processing the surface of a semiconductor workpiece, comprising:  
a fluid reservoir for holding a process fluid;